

Fig.1 AFM pictures

Indium Molybdenum Oxide (IMO) is a unique transparent conducting oxide (TCO) for application in IR imaging since it possesses the widest transmission in the spectral range extending from the visible to the Mid infrared to 25 microns. The transmittance % of a 50 nm thick film deposited on KBr substrate is shown in Fig. 2. The proprietary Pulsed Plasma Deposition (PPD) technique developed by Organic Spintronics allows obtaining thin films on organic semiconductors at room temperature. The proprietary low temperature deposition developed by Organic Spintronics allows to deposit IMO on organic semiconductors as shown in Fig. 3. (i.e. Aluminium Q₃)

Typical parameters of the IMO thin film obtained by PPD are the following:

Transmittance T%	Resistivity mΩ·cm	Sheet resistance Ω / □ (200nm)	Roughness nm r.m.s.	Temperature °C	Deposition rate Gun III @10Hz nm/min	Deposition rate Gun IV @100Hz nm/min	Substrate
90	0.4	30	12.4 ± 1.2	RT	8	300	PET Soft materials

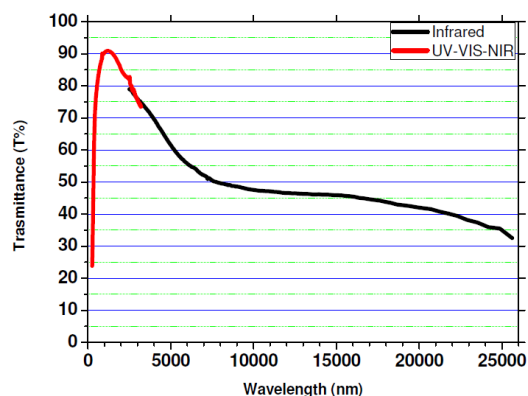


Fig. 2 UV-VIS-NIR-IR Transmittance of 50 nm thickness film on KBr

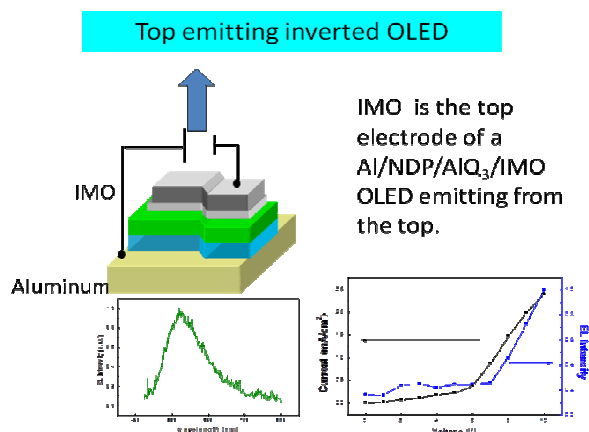


Fig. 3 Top-emitting inverted OLED (MRS spring meeting)